SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING METHOD

ABSTRACT

A substrate processing apparatus includes a stage for a substrate and an upper structure in a processing container, and an exhaust port that is open in a bottom wall of the processing container at a location outward of the stage in a plan view and is configured to exhaust an interior of the processing container. The upper structure includes a main body facing the stage, and a first annular portion extending downward from the main body to regulate a flow of a process gas. Further, the substrate processing apparatus includes a driver configured to change a distance between the stage and the upper structure, a first gas supply configured to supply the process gas into the processing container, a second annular portion extending upward from the bottom wall of the processing container to surround the first annular portion, and a second gas supply configured to supply an inert gas to a first gap, which is formed by the upper structure and the second annular portion and is in communication with the exhaust port.

(Fig. 1)